Honeywell Docket No. H0005631.68465 US -4780

Buchalter Docket No.: H9930-0105

IN THE CLAIMS

Claims 1-17: Canceled.

18. (Currently Amended) A planarization composition, consisting essentially of:

an o-cresol-based polymer compound and a resol phenolic resin:

at least one surfactant; and

a solvent system comprising at least one alcohol and at least one ether acetatebased solvent.

- (Previously Presented) The planarization composition of claim 18, wherein the ocresol-based polymer compound comprises a novolac polymer.
- (Original) The planarization composition of claim 18, wherein the at least one alcohol comprises a branched alcohol.
- (Original) The planarization composition of claim 20, wherein the branched alcohol comprises 2-propanol.
- (Previously Presented) The planarization composition of claim 18, wherein the at least one ether acetate-based solvent comprises propylene glycol methylether acetate (PGMEA).
- 23. Canceled
- (Previously Presented) The planarization composition of claim 18, wherein the surfactant comprises at least one hydrocarbon surfactant, at least one fluorocarbon surfactant or a combination thereof.
- (Previously Presented) The planarization composition of claim 24, wherein the at least one fluorocarbon surfactant comprises at least one fluoroaliphatic polymeric ester surfactant.
- (Previously Presented) A film comprising the planarization composition of claim 18, wherein at least some of the solvent system is removed.

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 (Previously Presented) A film comprising the planarization composition of claim 24, wherein at least some of the solvent system is removed.

Claims 28-29: Canceled.

- 30. (Original) A layered component, comprising:
 - a substrate having a surface topography; and
 - a planarization composition of claim 18, wherein the composition is coupled to the substrate.
- (Original) The layered component of claim 30, further comprising at least one additional layer of material or film.
- 32. (Original) A layered component, comprising:
 - a substrate having a surface topography; and
 - a layer comprising the film of claim 26, wherein the layer is coupled to the substrate.
- (Original) The layered component of claim 32, further comprising at least one additional layer of material or film.
- 34. (Original) A layered component, comprising:
 - a substrate having a surface topography; and
 - a layer comprising the film of claim 27, wherein the layer is coupled to the substrate.
- (Original) The layered component of claim 34, further comprising at least one additional layer of material or film.
- (Currently Amended) A method of forming a planarization composition, consisting essentially-of:
 - providing a structural constituent, wherein the structural constituent comprises an ocresol-based polymer compound and a resol phenolic resin;

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providing at least one surfactant:

providing a solvent system, wherein the solvent system comprises at least one alcohol and at least one ether acetate-based solvent; and

blending the structural constituent, the at least one surfactant and the solvent system to form a planarization composition.

Claims 37-40: Canceled.

- (Currently Amended) The method of claim [[40]] 36, wherein the alcohol-based solvent comprises 1-propanol or 2-propanol.
- (Currently Amended) The method of claim [[39]] 36, wherein the solvent system
 comprises propylene glycol methylether acetate (PGMEA), ethyl lactate, propylene
 glycol methyl ether, diethylene glycol, 2-propanol, acetone or a combination thereof.
- 43. (Original) The method of claim 36, wherein the intermolecular forces component comprises hydrogen bonding interactions, electrostatic forces, steric forces, dipoledipole interactions, dispersion forces, Van der Waals forces or combinations thereof.
- (Original) The method of claim 36, wherein the surface forces component comprises an interfacial surface tension.
- (Previously Presented) The method of claim 44, wherein the solvent system lowers the interfacial surface tension by at least 10%.
- (Previously Presented) The method of claim 45, wherein the solvent system lowers the interfacial surface tension by at least 20%.
- (Original) The method of claim 36, wherein the planarization composition comprises an apparent viscosity.
- (Previously Presented) The method of claim 47, wherein the solvent system lowers the apparent viscosity by at least 10%.

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 (Original) The method of claim 48, wherein the solvent system lowers the apparent viscosity by at least 30%.

50. Canceled.

51. (Previously Presented) The method of claim 36, wherein the surfactant

comprises at least one hydrocarbon surfactant, at least one fluorocarbon surfactant

or a combination thereof.

52. (Previously Presented) The method of claim 51, wherein the at least one

fluorocarbon surfactant comprises at least one fluoroaliphatic polymeric ester

surfactant.

53. (Previously Presented) A method of forming a film, comprising:

providing the planarization composition of claim 18; and

evaporating at least part of the solvent system to form a film.

54. (Original) The method of claim 53, wherein evaporating at least part of the solvent

system comprises applying a continuous source to the planarization composition.

55. (Original) The method of claim 54, wherein the continuous source comprises a heat

source.

 (Original) The method of claim 55, wherein the continuous source comprises an infrared source, an ultraviolet source, an electron-beam source and combinations

thereof.

Claims 57-75: Canceled.

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